Accepted Manuscript

Self-aligned photolithography for the fabrication of flexible transparent high-voltage thin film transistors, diodes and inverters



Yonghui Zhang, Zengxia Mei, Wenxing Huo, Tao Wang, Huili Liang, Xiaolong Du

PII:	S0167-9317(18)30368-X
DOI:	doi:10.1016/j.mee.2018.07.021
Reference:	MEE 10845
To appear in:	Microelectronic Engineering
Received date:	1 June 2018
Revised date:	10 July 2018
Accepted date:	30 July 2018

Please cite this article as: Yonghui Zhang, Zengxia Mei, Wenxing Huo, Tao Wang, Huili Liang, Xiaolong Du , Self-aligned photolithography for the fabrication of flexible transparent high-voltage thin film transistors, diodes and inverters. Mee (2018), doi:10.1016/j.mee.2018.07.021

This is a PDF file of an unedited manuscript that has been accepted for publication. As a service to our customers we are providing this early version of the manuscript. The manuscript will undergo copyediting, typesetting, and review of the resulting proof before it is published in its final form. Please note that during the production process errors may be discovered which could affect the content, and all legal disclaimers that apply to the journal pertain.

ACCEPTED MANUSCRIPT

Self-Aligned Photolithography for the Fabrication of Flexible Transparent High-Voltage Thin Film Transistors, Diodes and Inverters

Yonghui Zhang^{a,b}, Zengxia Mei^{a,*} zxmei@iphy.ac.cn, Wenxing Huo^{a,b}, Tao Wang^a, Huili Liang^a, and Xiaolong Du^{a,b,*} xldu@iphy.ac.cn

^aBeijing National Laboratory for Condensed Matter Physics, Institute of Physics, Chinese Academy of Sciences, Beijing 100190, P. R. China ^bSchool of Physical Sciences, University of Chinese Academy of Sciences, Beijing 100049, P. R. China

*Corresponding authors.

Scr

Download English Version:

https://daneshyari.com/en/article/6942358

Download Persian Version:

https://daneshyari.com/article/6942358

Daneshyari.com